



+/- RESIST STRIP & CLEAN

MODEL RSSx126

DESCRIPTION: MODEL RSSx126

The highly efficient Model RSSx126 is the ideal for Stripping and Cleaning Photoresist both Positive & Negative on Photomask, Wafers and Substrates. The very reliable and cost effective system utilizes proven assortment of cleaning technologies. The RSSx126 can be configured with several cleaning options from Brush for Sulfuric Peroxide, Surfactant, and/or DI-H₂O; Megasonic Nozzle for DI-H₂O or Chemistries; low pressure nozzles for chemistry dispenses; heaters for chemistries and DI-H₂O; and much more. The Rapid and Effective Drying technique combines Variable Spin Speeds; optional Heated DI-H₂O; and Nitrogen Assist. The System is very safe, having "Rinse to pH" before access to the substrate to minimize exposure to chemistries.

FEATURES: CONTROL & SAFETY

- System Designed for Significant Control & Safety
- Up to Nine by Nine (9x9) Inch/300mm Diameter Substrate Compatibility.
- Main Spindle Assembly having DC Brushless Servo Motor for precise speed control & indexing.
- Adjustable Arm Speed and Travel Positions with Arms of Teflon Coated Stainless Steel.
- Radially Exhausted Chamber for Maximum Laminar Flow with N₂ feed at Top of the lid.
- DI-H₂O Heater for Clean & Dry Assist.
- Process containment of chemically compatible material either PVDF or optional PTFE.
- Stand-alone Polypropylene Cabinet.
- Microprocessor Control Capable of Retaining Thirty (30) Recipes having thirty (30) Steps each in Memory. Both number of Recipes & Steps are expandable upon request.
- Built in Safety Interlocks & Double Containment.
- Rinse to pH of entire process area & substrate with interlocks to prohibit access to process area & control Drain and Spindle Speed till safe.
- Push Button Lid Open/Close.
- Touch Screen Graphic User Interface (GUI) with Ease of Programming & Security Lockouts with On-Screen Error Reporting.
- Drain Diverter Valves for Chemical & Rinse DI-H₂O
- Designed to SEMI S2/S8 Guidelines



MODEL
RSSx126



TYPICAL
CLEANING
CHAMBER
& CHUCK
(3 OF 4
ARMS
SHOWN)

CHEMISTRY:

- Nano-Strip[®], Piranha: (H₂SO₄ + H₂SO₅ + H₂O₂ + H₂O)

OPTIONS: UP TO FOUR OSCILLATING DISPENSE ARMS

- Various sizes & types of chucks for Wafers, Photomask, and other Substrates.
- Auto Up/Down Oscillating Adjustable Self Cleaning Brush Assembly for chemical, Surfactant, & DI-H₂O Dispenses.
- Fixed or Oscillating Low Pressure Dispense with various Nozzles for DI-H₂O &/or Chemistries.
- Chemical Cabinet with weight Scale Dispense Canisters & Pump.
- Heater for Chemical Dispenses.
- Secondary Containment With Leak Detection
- Oscillating Megasonic DI Water or Chemical Dispense Arm.
- FM4910 Fire Retardant Cabinet & Process Area Materials

ULTRA *t* Equipment Company, Inc.
41980 Christy Street, Fremont, CA 94538
TEL: (510) 440-3900 FAX: (510) 440-3920
URL: www.ultrat.com